# LabAdviser update: 23/10 2019

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| Updated Subject  | Contributor | Link to the updated pages |
| **InP etch with HBr chemistry**Optimized to get low surface roughness | **Aurimas Sakanas @Fotonik** |  [/Etch/III-V\_ICP/InP-InGaAsP-InGaAs#InP\_etch\_with\_HBr\_chemistry](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/III-V_ICP/InP-InGaAsP-InGaAs#InP_etch_with_HBr_chemistry) |
| **Temescal – Au deposition**Optimizing Au deposition in the Temescal depositin system | **Patama Pholprasit and Evgeniy Shkondin @Nanolab** | [/Thin\_film\_deposition/Temescal#2.\_Testing\_July.2FAugust\_2019\_by\_Evgeniy\_Shkondin\_and\_Patama\_Pholprasit](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Temescal#2._Testing_July.2FAugust_2019_by_Evgeniy_Shkondin_and_Patama_Pholprasit) |
| **Lithography – Descum**Ashing times for some descum processes on Plasma Asher 1, using 2” wafers | **Jesper Hanberg** | [Lithography/Descum](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Descum) |
| **Al2O3 wet etch**Al2O3 wet etch rate in different HF solutions | **Evgeniy Shkondin @Nanolab** | [/Etch/Aluminum\_Oxide/Al2O3\_Etch\_using\_HF](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Aluminum_Oxide/Al2O3_Etch_using_HF) |
| **Four-Point probe from Jandal**Updated information about the new Four-Point probe from Jandal | **Patama Pholprasit @Nanolab** | [Characterization/Four-Point\_Probe#Four-Point\_Probe\_from\_Jandel](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Four-Point_Probe#Four-Point_Probe_from_Jandel) |
| **Mask ordering**Procedure regarding mask ordering has been changed. In the future masks has to be ordered from Compugraphics using Procure. Guidance how to do this is now available. **Please note that the mask definitions are different from what it used to be.** | **Karen Birkelund****@Nanolab** | [Maskebestilling\_i\_Procure.pdf](http://labadviser.nanolab.dtu.dk/images/2/20/Maskebestilling_i_Procure.pdf)Link i Labadviser:[Pattern\_Design#Mask\_Ordering\_and\_Fabrication](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Pattern_Design#Mask_Ordering_and_Fabrication) |

# Equipment Manuals updated in LabManager (since 13rd of August):

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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| 5. 3. 1.35) Manual for Developer: TMAH Manual, ver 2.3 |
| 5. 3. 7.48) Manual for SEM Supra 3, ver 1.2 |
| 5. 3. 3.12) Manual for IBE/IBSD Ionfab 300, ver 1.8 |
| 5. 3. 2.22) Manual for ALD 2 (PEALD), ver 2.1 |
| 5. 3. 6.06) Manual for Polymer Injection Molding, ver 6 |
| 5. 3. 1.43) Manual for Spin coater: RCD8, ver 1.2 |
| 5. 3. 1.44) Manual for Spin Coater: Gamma UV, ver 1.2 |
| 5. 3. 5.18) Manual for III-V oxidation furnace (C2), ver 1 |
| 5. 3. 1.17) Manual for DUV Stepper., ver 3.1 |
| 5. 3. 1.30) Manual for SÜSS Spinner-Stepper., ver 3.1 |
| 5. 3. 1.36) Manual for Developer TMAH Stepper., ver 3.1 |
| 5. 3. 1.38) Manual for Hotplate: 90-110C, ver 2.1 |
| 5. 3. 1.39) Manual for Developer TMAH UV-lithography, ver 3.1 |
| 5. 3. 1.50) Manual for Spin coater: Labspin 02, ver 2 |
| 5. 3. 1.51) Manual for Spin coater: Labspin 03, ver 2 |
| 5. 3. 6.15) Manual for X-Ray Focal Spot, ver 1 |